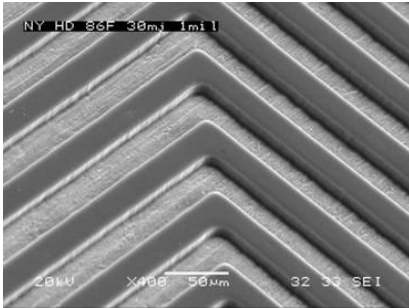


Photoposit™ SN 68V Photoresist

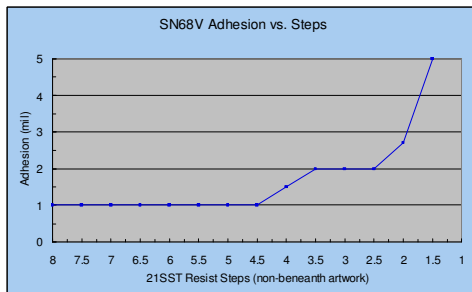
A robust, high-yielding, fine-line, low-cost photoresist



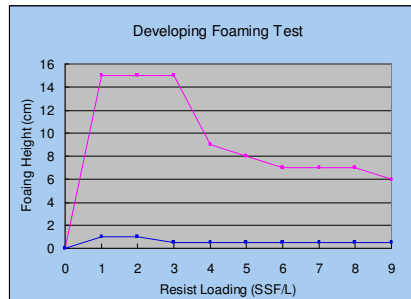
Photoposit™ SN 68V Photoresist has been developed to address industry demands for a robust, high-yielding, fine-line, low-cost photoresist, that can be utilized in today's manual and automatic exposure equipment at optimum productivity levels. Photoposit™ SN 68V Photoresist has been optimized for use on vertical double-sided roller coaters and is supplied at a viscosity appropriate for roller coating.

Features and benefit

- Excellent coating rheology
- 24~48 hours of stackability
- Unmatched resistance to mechanical and handling damage
- Excellent chemical resistance to acid-based etchants
- Resolution capability 25 micron lines and spaces
- Low foaming. Little, or no need for addition of antifoam to the developer
- Much less sludge generated during developing
- Extremely wide processing window
- Improved yield
- Significant savings over dry film
- Reduced labor and waste treatment costs



Excellent adhesion vs photo speed



Low foaming in developing